

Amendments to the Specification

Please replace the paragraph on page 1, lines 5-8 with the following paragraph:

1. Field of the Invention

The present invention relates generally to an improved chemical vapor deposition ~~process~~ apparatus, and particularly to a ~~process~~ chemical vapor deposition apparatus for the deposition of tungsten silicide from dichlorosilane (DCS), ~~and an apparatus for performing the same.~~